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APPLICATION NO.	PILENO DATE	PIRST NAMED INVENTOR	ATTORNET BOCKET NO.	CONFIRMATION NO.	
10/585,161	03/28/2007	Benjamin B. Yellen	46528-5090-00-US	8334	
29973 7590 9917/2010 DRINKER BIDDLE & REATH ATTN: INTELLECTUAL PROPERTY GROUP ONE LOGAN SQUARE, SUITIT 2000 PHILADEL PHILA PA 19103-6996			EXAM	EXAMINER	
			ROSASCO, STEPHEN D		
			ART UNIT	PAPER NUMBER	
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			NOTIFICATION DATE	DELIVERY MODE	
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## Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

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## Application No. Applicant(s) 10/585,161 YELLEN ET AL. Office Action Summary Examiner Art Unit Stephen Rosasco -- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --Period for Reply A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS. WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b). Status 1) Responsive to communication(s) filed on 14 October 2008. 2a) This action is FINAL. 2b) This action is non-final. 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213. Disposition of Claims 4) Claim(s) 1-8 is/are pending in the application

5) Claim(s) is/are allowed.				
jected to by the Examiner.				
yance. See 37 CFR 1.85(a).				
ing(s) is objected to. See 37 CFR 1.121(d).				
ned Office Action or form PTO-152.				
. § 119(a)-(d) or (f).				
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Art Unit: 1795

## Detailed Action

Allowability is indicated for claim 8.

The following is an examiner's statement of reasons for allowance for claim 8: the prior art of record to Chen et al. (20040150865) teaches a programmable mask comprising: a plurality of optical modulators arranged in an array, said plurality of optical modulators each including at least one nano-particle; and a control arrangement operatively coupled to said optical modulators, said control arrangement applying a stimulus to said nano-particles to thereby cause said nano-particles to change optical properties.

And wherein said control arrangement applies an electrical magnetic stimulus to said nano-particles.

However the prior art of record does not teach the method of claim 8, including fabricating a multi-component pattern comprising defining multiple regions of localized magnetic field maxima and minima on a substrate; and then applying magnetic nanoparticles to the substrate so that the magnetic nanoparticles aggregate on the first set of regions of localized magnetic field maxima and avoid regions of localized magnetic field minima.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance"

Art Unit: 1795

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

Claim 1 is rejected under 35 U.S.C. 102(e) as being anticipated by Chen et al. (20040150865).

Chen, et al. (see especially claim 3) addresses claim 1, including a programmable mask comprising: a plurality of optical modulators arranged in an array, said plurality of optical modulators each including at least one nano-particle; and a control arrangement operatively coupled to said optical modulators, said control arrangement applying a stimulus to said nano-particles to thereby cause said nano-particles to change optical properties.

And wherein said control arrangement applies an electrical magnetic stimulus to said nano-particles.

Art Unit: 1795

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 2-7 are rejected under 35 U.S.C. 103(a) as being unpatentable over Chen et al. (20040150865) in view of Raguse et al. (6.984,265).

Regarding claims 2-7 Chen et al. is included here as discussed above.

Chen et al. also teach that the nano-particles can be arranged in an array forming a plurality of discrete optical modulators. The stimulating may comprise applying a current, voltage or field to said nano-particles.

Therefore, Chen et al. teach applying some type of field to the magnetic nanoparticles.

The teachings of Chen et al. differ from those of the applicant in that the applicant teaches applying a magnetic field to produce localized magnetic field maxima and a substantially uniform magnetic field.

Art Unit: 1795

Raguse et al. disclose (see claims 24-30) a <u>nanoparticle</u> film comprising a three dimensional cross-linked array of <u>nanoparticles</u> and linker molecules in which the nanoparticle film is coherent, robust and self supporting.

And in claim 25, in which the <u>nanoparticles</u> are formed from material selected from the group consisting of metallic and <u>magnetic</u> materials.

Raguse et al. also teach that the <u>nanoparticle</u> is formed of a material such that it responds to an externally applied electric or magnetic field.

It would have been obvious to one having ordinary skill in the art to modify the teachings of Chen et al. and apply a field to the magnetic nanoparticle pattern as taught by Raguse et al. to adjust the pattern in order to make the claimed invention because it would have been obvious to one in the art to apply any field necessary to produce the desired arrangement of the magnetic nanoparticles pattern.

## Conclusion

Any inquiry concerning this communication or earlier communications from the Examiner should be directed to Stephen Rosasco whose telephone number is (571) 272-1389. The Examiner can normally be reached Monday-Friday, from 8:00 AM to 4:30 PM. The Examiner's supervisor, Mark Huff, can be reached on (571) 272-1385. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306.

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/S. Rosasco/ Primary Examiner, Art Unit 1795

S.Rosasco 05/11/10